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Patent
Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)
Kazuya KAMON) Group Art Unit: 1756
Application No.: 09/320,946) Examiner: S. Mohamedulla
Filed: May 26, 1999) Confirmation No.: 5658
For: PHOTOMASK, FABRICATION)
METHOD OF PHOTOMASK, AND)
FABRICATION METHOD OF)
SEMICONDUCTOR INTEGRATED)
CIRCUIT)

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GROUP 1700

AMENDMENT UNDER 37 C.F.R. § 1.111

Assistant Commissioner for Patents
Washington, D.C. 20231

Date: May 20, 2003

Sir:

This Amendment responds to the Office Action dated November 20, 2002 (Paper No. 21). Concurrently filed with this amendment is a Petition for Extension of Time for three months. Please amend the above-noted application as follows:

IN THE CLAIMS:

Please cancel claims 12, 22, 40 and 48 without prejudice, replace claims 2, 5, 7, 23, 31, 32, 36, 37, 41-43, and add new claims 50 and 51 as follows:

2. (Twice Amended) A photomask comprising:
a transparent substrate;

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